

PHOTORESIST COMPOSITION

Patent number: JP9054432
Publication date: 1997-02-25
Inventor: HASHIMOTO YUTAKA; TANAKA KAZUYOSHI
Applicant: DAINIPPON INK & CHEM INC
Classification:
- **international:** G03F7/027; G03F7/038; G03F7/075; H01L21/027
- **european:**
Application number: JP19950210641 19950818
Priority number(s):

[Report a data error here](#)

Abstract of JP9054432

PROBLEM TO BE SOLVED: To improve the coating performance, soln. stability, etc., of a photoresist compsn.

SOLUTION: This compsn. contains a copolymer of a (meth)acrylate monomer having a fluoroalkyl group with an ethylenically unsatd. monomer having a silicone chain and a (meth)acrylate monomer having a polyoxyalkylene group. This compsn. does not cause unevenness in the thickness of a coating film or striation at the time of spin coating and enables uniform coating.

Data supplied from the **esp@cenet** database - Patent Abstracts of Japan